

Photoemission research at Cornell University: recent advances and future perspectives

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R&D areas

- Photocathode lab hardware upgrades and modifications
 - Alkali antimonides growth chambers;
 - New High Voltage DC cryogun;
 - New substrates holders (INFN miniplug REF/TRANS , Omicron-like);
 - Mott polarimeter;
- Numerical simulations
 - Alkali-antimonide Monte Carlo photoemission simulation;
 - Micro-sized tips;
- Cathode growth and characterization
 - La:BaSnO₃;
 - CsTe over GaAs;
- High Brightness
 - X-FELs;
 - UED;

- High intensity
 - ERLs;
 - Electron cooling;
- Polarized sources
 - Colliders;



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Accelerator-based Sciences and ERL R&D aimed at high average currents

Alkali antimonides proved their ruggedness in the ERL injector prototype



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DC Gun



14

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Na₂KSb: 48 hours long run



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...and high brightness for X-FELs.

arrival time (ps)

High rep. rate FEL (LCLS-II) injector requirements

- Vary all relevant magnet, cavity settings
- Vary laser shaping: truncation fraction, crystal angles

Q (pC)	I _{peak} Target (A)	ε _n Target (95%, μm)
20	5	0.25
100	10	0.40
300	30	0.60



				Q (pC)	I _{peak} (A)	ε _n (95%, μm)	ε _{n,th} /ε _n
Ideal Shape				20	5	H: 0.18, V: 0.19	60%
				100	11.5	H: 0.32, V: 0.30	80%
			Measured Shape	300	32	H: 0.62, V: 0.60	70%
•	(<u>u</u>) <u>u</u> ⁻ 0.4 0.2 0,1 0,2 0,1 0,2 0,2 0,1 0,2 0,2 0,2 0,2 0,2 0,2 0,2 0,2	300 pC 300 pC	 	35 300 pC 30 25 (Y) 20 15 10 20 pC 5 		• data • GPT - GPT - 20 - 10 0	

The transverse laser shape can make a difference

C. Gulliford, A. Bartnik, I. Bazarov, B. Dunham, L. Cultrera, Appl. Phys. Lett. 106 (2015) 094101



Photocathode Lab





2nd growth system

Our 2nd growth chamber has been completely rebuilt and recommissioned and is now our production chamber to deliver cathodes for our electron guns (Cs₃Sb, CsK₂Sb, Na₂KSb)





INFN/DESY/LBNL miniplug



Interface to grow on the "miniplug" in use at INFN/DESY/LBNL and in our new Cornell HV DC cryogenic gun

Prototype of transmission mode



Back illumination makes brighter electron beams!

Appl. Phys. Lett. 108, 124105 (2016)

Glass substrate



~3 micron laser spot size



Cornell Laboratory for Accelerator-based Sciences and Transverse Energy Meter (TEmeter) Education (CLASSE)

- Measure Mean Transverse Energy (MTE)
- Cryogenically cooling capacity @ 90K with LN2
- Voltage up to 20kV (~4-5MV/m) with gap (4-5mm)
- Compact device ~ 30" tall and 20" long







Alkali antimonide near threshold of emission (TEmeter voltage scan example)





Cool the cathode to cool the beam

At about 0.25 μm/mm rms we almost touched the bottom of QE... <u>Electron finite temperature</u> sets a lower limit to the minimum intrinsic achievable emittance (0.22 μm/mm rms)

What happen if we cool the cathode to cryogenic temperature?

As **T lowers from 300 K to 90 K**, MTE should lowers from **25** to **8** meV and the minimum intrinsic emittance from 0.22 to 0.12 μ m/mm rms 10^{-2} 60 ~0.3 mm mrad Cs₃Sb Cs₃Sb 50+ 6e-4 10^{-°} 40 MTE [meV] 붱 10⁻ 30 ~25 meV at 300 K 7e-5 MTEx at LN2 ~0.17 mm mrad 20 MTEy at LN2 10⁻⁵ MTEx at RT MTEy at RT @ 690 nm 10 ~8 meV at 90 K 10⁻⁶L 2.5 3 3.5 4.5 5 *`*600 650 700 750 800 voltage [kV] Wavelength (nm) 200 K equiv. temp. **Combining the benefit of**

"near threshold"+ "cryo-temperature"+ "transmission" to minimize initial electron beam phase space L. Cultrera et al., Phys. Rev. ST – Acc. Beams **18** (2015) 113401 H. Lee et al., Rev. Sci. Instrum. **86** (2015) 073309

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HV DC Cryogun @ 20 K

electrode







≥10 MV/m DC field doable



- The gun was designed to reach 20 K at the cathode
- Electric field at or larger than 10 MV/m •
- Beam energy above 200 keV



HV DC Cryogun @ 43 K





Cs₃Sb first beam



T = 300K, E = 230keV, V = 11.5MV/m T = 45K, E = 190keV, V = 9.5MV/m



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- Cs₃Sb grown with sequential growth over polished SS;
- Time constraints delayed detailed emission studies;
- Demonstrated the first beam at RT and 45 K;
- Gun is being relocated in a new lab;
- Cathode loading mechanism is being revisited;

14



Cryocooling alkali antimonides



Cornell Laboratory for Accelerator-based Sciences and **Comparison with experiment and predictions** Education (CLASSE)

Parameter	Symbol	Value		
Band gap at room	$E_{-}(297 \text{ K})$	1.6 eV^4		
temperature (297 K)	<i>Lg</i> (201 II)	1.0 0 1		
Bulk electron affinity	χ	0.45 eV^4		
Conduction band				
effective mass (Γ	$m^*_{\Gamma,c}$	$0.23 \ m_e \ ^{\star 8}$		
valley)				
Valence band				
effective mass (Γ	$m^*_{\Gamma,v}$	$0.36 \ m_e^{-\star 8}$		
valley)				
Longitudinal optical	ħ	$0.022 \text{ eV}^{5,23}$		
phonon energy	$n\omega_{LO}$	0.022 ev		
Doping density	N	$7.5 \times 10^{20} \text{ cm}^{-3}$ 10		
(Sakata)	1 V A0	$1.5 \times 10^{-1} \text{ cm}^{-1}$		
Doping density	N	$10^{19} - 3 10$		
(Spicer)	IVA0	10 cm		
Acceptor energy	$F_{1} = F_{1}$	0.20 eV^{10}		
level (Sakata)	$E_A - E_V$	0.23 CV		
Static dielectric	6	8262		
constant (Spicer)	c_s	0.2 €0		
Static dielectric	c	11.4 60		
constant (Sakata)	c_s	11.4 0		
High frequency	E	$5 \epsilon c^2$		
dielectric constant	€∞	0.60		
Damping coefficient	Г	$1.58 \times 10^{15} \frac{\text{rad}^2}{\text{s}}$		
Resonance angular	(J=	$4.92 \times 10^{15} \text{ rad } 2$		
frequency	ω_T	4.22×10 s		
Acceptor level				
resonance angular	ω_T'	$1.23 \times 10^{15} \frac{\mathrm{rad}}{\mathrm{s}}$		
frequency				
VBM at surface	D	-0.35 eV (ad-hoc)		
(with respect to E_F)	Б			
Substrate refractive	2	1.5		
index	n_s	1.0		
Substrate work	¢	4.4 eV^{24}		
function	φs	4.4 6 V		
Electron-phonon	$\Delta E_{\pi D}$	0.1 eV^{14}		
coupling strength	ΔDZP	0.1 6 V		

Interplay of a large number of parameters Qualitative agreement with experiment

Difficult to treat electron emission at electron energies well below 1 eV. Sudden approximation is not valid anymore. Many non-uniformities (roughness, φ) can affect MTE



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Pristine surfaces

Enormous progresses have been made in realizing smooth surfaces of alkali antimonides Their surface still cannot be considered atomically flat and uniform

BaSnO₃

- Transparent conducting oxide
- Can be n-doped with La up to 10²⁰ cm⁻³ (x=4%, degenerate semiconductor)
- Stable in air



ARPES measurements revealed faint signals from non dispersive states near the Fermi Energy (surface states? Defects?)



Epitaxially grown using MBE => pristine surfaces



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(data courtesy of Ed Lochocki and Hanjong Paik) 17



QE and MTE

- The very sample used to collect the ARPES spectrum was moved into our UHV system;
- Light sources photon energies are $\overset{\text{III}}{\text{O}}$ below the required range ($\phi > 4.3$) eV)

So far MTFs measurements have been difficult to perform because of the poor s/n ratio due to:

- low intensity of the electron beam signal;
- insufficient filtering of the ٠ diffuse laser light;
- Field emitter; ٠









Cornell Laboratory for Accelerator-based Sciences and Leverage the electric field





ERL FFAG Experiment





CsTe on GaAs and polarized electron beams



Valence band maximum

The BNL Linac-Ring option for EIC need electron beams with:

- larger than **70% polarization**
- Average electron currents up to **50 mA**
- GaAs cannot provide such intensities



M. Kuriki, P3 Workshop 2014, Berkeley

- LESS VACUUM SENSITIVE COMPARED TO Cs-O?

Fermi level

Valence band maximum of film

- WHAT HAPPEN TO THE ELECTRON BEAM POLARIZATION?
- CAN BE STORED/TRANSPORTED IN A SUITCASE?

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CsTe on GaAs

GaAs substrate samples p-type Zn doped 1e18 cm-3 Wet etch to remove oxide and passivate surface @532 nm QE 1.5% Cs+Te @532 nm QE 0.5% -H₂SO₄:H₂O₂:H₂O (20:1:1) 2 min @ RT 10⁻⁸ · Chotocurrent (A) -HCI:iPA (20:80) 3 min @ RT Cs 10⁻⁹ 1 Te GaAs Sample 1 10⁻¹⁰ 84.0746 **Rough surface** Cs Cs 10⁻¹ Many pits 50 40 Thickness (nm) 631 µm 30 20 10x Te 10 Ω -346.17 120 849 um Sub. Temp. (C) Heat cleaning at 400 C overnight 100 Substrate Room Temperature Cs activation yields ~3% QE @ 532nm heater OFF Surface is clean enough to perform activation!! 80 60 5000 10000 15000 0 Time (s) We now skip the first step of etching... QE after Cs is lower but we have no more surface pitting



CsTe on GaAs

- Auger spectroscopy confirms the presence of Cs and Te over the GaAs surface
- Ga ans As peaks are still visible meaning that the CsTe layer is thinner than few nm
- C and O peaks likely coming from the egun filament





- We do NOT see an emission threshold shift
- We do **NOT** get the high QE previously reported by Japanese group

Patchy coverage of the surface?



CsTe on GaAs

Vacuum level is below 1e-10 Torr

Alkali antimonide do not experience QE degradation



Fit with 2 exponential decay (fast< 1hour, slow several hours): -fast decays have same order of magnitude;

-slow decays component time constant improved by a factor 3 (~24 hours);



Mott scattering polarimeter

We loan from Jlab a retarding field Mott polarimeter that was designed and used at SLAC to study the generation of polarized electron beam from strained GaAs and other III-V superlattices.

Spin-orbit interaction => asymmetry in scattering





Count rate vs ELW @ V threshold= 5.3 mV, Channeltron bias=2.5 kV, photocurrent=0.8 nA





Kamper et al, PRL **59**, 2788 (1987)



TABLE II. Work functions for CrO₂ surfaces.

	$\Phi_{unrelaxed} \ (eV)$	$\Phi_{relaxed} \ (eV)$
(100) Cr	3.64	3.40
(100) O	6.38	6.23

Attema et al, PRB 77, 165109 (2008)

Stable material Lowest workfunction is 3.4eV Require UV light

CrO₂

Up to 4.4 eV photon energy only one spin can be photoexcited => 100% polarization



Spin filters

Spin dependent barrier below Tc





Can we make real electron beams?



FIG. 3. Field-emission model for EuS on W for a typical field $F = 2.5 \times 10^7$ V/cm. In the image force potential α is $(\epsilon_{opt} - 1)/(\epsilon_{opt} + 1)$ with $\epsilon_{opt} = 5.2$ (Ref. 22). ψ_+ is the electron affinity of the lower split conduction band, χ the photothreshold, and ψ_W and ψ_{EuS} the work functions of W and EuS.

Field emission experiment W/EuS date back in 1972

Required operation at **cryo-temperatures to get EuS<Tc** Polarization of **89±7 %** was measured at **21K**

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Cornell Laboratory for Accelerator-based Sciences and Upcoming Photogun Laboratory Education (CLASSE)





Summary

- Identified venues producing immediate benefits for existing/future X-FELs and UED;
 - Near threshold operation;
 - Cryocooling, micron sized laser spot;
- Cornell infrastructure provide closed loop:

Looking forward to new materials for improved performances

- Improve our interactions with material scientist



Thanks for your attention!

The Cornell team:

I. Bazarov, J. Maxson, A. Bartnik, C. Gulliford, H. Lee, A. Galdi, J. Kwan Bae, W. Li, C. Pierce, T. Moore, S. McBride, C. Xu, R. Doane



Beam Brightness

Motion along longitudinal (acceleration) and transverse direction is decoupled

$$\frac{B_{n,av}}{f} = q^{-1} \frac{1}{(mc)^2} \int \rho_4'^2 dx dy dp_x dp_y$$

$$MTE = kT_e = m_e c^2 (\varepsilon_{n,x})^2$$

For **"pancake"** distribution (transverse >> longitudinal size) it can be shown that



<u>Electric field</u> at photocathode surface and <u>equivalent temperature</u> of electrons are limiting the maximum microscopic brightness

If the bunch charge is sufficiently low that no virtual cathode instability effect will be induced, further improvement of the 4D brightness can be achieved by using relatively long laser pulses (10s of ps) and very small laser spot sizes (<100 μ m)



I. V. Bazarov et al., Phys. Rev. Lett. 102, 104801 (2009)



Two different problems

Solving the Poisson equation....



3 steps Monte Carlo is used to compute photoemission



Difficult to treat electron emission at electron energies well below 1 eV. Sudden approximation is likely not valid anymore and different types of <u>non-uniformities</u> can affect the transverse momentum of electrons;

Emission

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Transmission mode cathodes

H. Lee et al., Appl. Phys. Lett. 108, (2016) 124105



Increase the number of e-ph scattering

lower MTE (and intrinsic emittance)

Increase the average e- travel distance by operating them in transmission rather than reflection mode



transmission mode configuration easily allows the realization of **very small laser spot** on the cathode surface





MTE is 20% smaller !!





How well can we shape the laser beam?



Liquid crystal array is used as mask to attenuate the transverse distribution of the laser "point to point" to match the desired laser profile



- Easy to implement
- Fast feedback
- Above 30% efficiency (flat top)

Damage threshold 2.6 W/cm² average power 101 MW/cm² peak power



J. Maxson, A. Bartnik, I. Bazarov, Applied Physics Letters 105 (2014) 171109

J. Maxson, H. Lee, A. C. Bartnik, J. Kiefer, and I. Bazarov, Phys. Rev. ST Accel. Beams 18, 023401 (2015)



La:BaSnO3

- Preliminary TE meter measurements with 410 nm-450 nm wavelength
- The voltage scans have been performed using a 200 um pinhole
- We plan to repeat the measurement on a second sample.





Surprise! The machine tripped **10x more often** with only the gun.

Gun Test Beamline

 Upon further inspection, an error was discovered in our previous reasoning— it was possibly always the gun.



With ion clearing electrode 24 hours at 20 mA with no trips!!